IN THE WHITED STATES PATENT AND TRADEMARK OFFICE

Application Serial No	
Filing Date	
Inventor	Basceri et al.
Assignee	Micron Technology, Inc.
Group Art Unit	1762
Examiner	E. Fuller
Attorney's Docket No	
Title: Chemical Vapor Deposition Method	ds of Forming Barium Strontium Titanate
Comprising Dielectric Layers	

INFORMATION DISCLOSURE STATEMENT

To:

Mail Stop RCE

Commissioner for Patents

P.O. Box 1450

Alexandria, VA 22313-1450

From:

Jennifer J. Taylor, Ph.D.

(Tel. 509-624-4276; Fax 509-838-3424)

Wells St. John P.S.

601 W. First Avenue, Suite 1300

Spokane, WA 99201-3828

Dear Sir:

The Examiner's attention is directed to the references which are listed on the attached Form PTO-1449 and copies of which are attached.

Citation of these references is respectfully requested.

Respectfully submitted,

Datad.

By:

Tennif

Tavlør

Reg.No∕. ₄

Sheet 1 of 3 ATTY. DOCKET NO. SERIAL NO. MI22-1724 09/905,286 U.S. DEPARTMENT OF COMMERCE PATENT AND TRADEMARK OFFICE Form PTO-1449 APPLICANT LIST OF ART CITED BY APPLICANT Cem Basceri et al. (Use several sheets if necessary) FILING DATE **GROUP** JUL 0 9 2004 July 13, 2001 1762 U.S. PATENT DOCUMENTS Filing Date Subclass *Examiner Date Name ΑА 4,261,698 04/81 Carr et al. AB 09/87 Roppel et al. 4.691.662 AC Takasu et al. 5,261,961 11/93 AD 5,270,241 12/93 Dennison et al. ΑE Takasaki et al. 5,312,783 05/94 AF 5,392,189 02/95 Fazan et al. AG 5,395,771 03/95 Nakato AΗ 11/95 5,468,687 Carl et al. AI 5,525,156 06/96 Manada et al. 03/97 5,614,018 Azuma et al. AΚ 5,656,329 08/97 Hampden-Smith ΑL 5,663,089 09/97 Tomozawa et al. FOREIGN PATENT DOCUMENTS Date Class Subclass Translation Country No AM EP 0 030 798 06/81 EPO AN GB 2 194 555 A 03/88 United Kingdom ΑO 03/89 **EPO** EP 0 306 069 A2 ΑP EP 0 388 957 A2 09/90 EPO ΛQ JP2250970 10/90 Japan OTHER REFERENCES (including Author, Title, Date, Pertinent Pages, Etc.) Aoyama et al., Leakage Current Mechanism of Amorphous and Polycrystalline Ta₂O₅ Films Grown by Chemical Vapor Deposition, 143 J. ELECTROCHEM Soc., No. 3, pp 977-983 (March 1996). AS Stemmer et al., Accommodation of nonstoichiometry in (100) fiber-textured (Ba_xSr_{1-x})Ti_{1+y}O_{3+z} thin films grown by chemical vapor deposition, 74 APPL. PHYS. LETT., No. 17, pp. 2432-2434 (26 April 1999). AΤ Streiffer et al., Ferroelectricity in thin films: The dielectric response of fiber-textured (Ba_xSr_{1.x})Ti_{1+y}O_{3+z} thin films grown by chemical vapor deposition, 86 J. APPL. PHYS. No. 8, pp. 4565-4575 (15 October 1999).

*EXAMINER: Initial if reference considered, whether or not citation is in conformance with MPEP 609; Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.

EXAMINER

DATE CONSIDERED

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